

SYSTEM FOR GENERATING TWO-DIMENSIONAL MASKS FROM A THREE-DIMENSIONAL MODEL USING TOPOLOGICAL ANALYSIS

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ABSTRACT

A method of generating two-dimensional masks from a three-dimensional model comprises providing a three-dimensional model representing a micro-electro-mechanical structure for manufacture and a description of process mask requirements, reducing the three-dimensional model to a topological description of unique cross sections, and selecting candidate masks from the unique cross sections and the cross section topology. The method further can comprise reconciling the candidate masks based on the process mask requirements description to produce two-dimensional process masks.